

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1829	SERIAL NO. Filed Herewith	11046 U.S. PTO 10/07/00 02/05/02	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT H. Daniel Dulman			
				FILING DATE Filed Herewith			
U.S. PATENT DOCUMENTS							
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
JL	AA	5,208,125	Lowrey et al.	430	5		
JL	AB	5,217,830	Lowrey	430	5		
JL	AC	5,308,721	Garofalo et al.	430	5		
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	AM						
	AN						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
JL	AO	Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method", 19th Annual BACUS Sympos. on Photomask Technology, Monterey, CA, Sept. 1999, SPIE Vol. 3873, pp. 288-296.					
JL	AP	Kobayashi, S. et al., "Development of Simplified Process for KrF Excimer Half-Tone Mask with Chrome-Shielding Method (II)", 20th Annual BACUS Sympos. on Photomask Technology, Proceedings of SPIE Vol. 4186 (2001), pp. 801-809					
JL	AQ	Lim, S. et al., "Application of Alternating Phase-Shifting Masks to Sub-Quarter Micron Contact Holes", SPIE Vol. 2726, Feb. 1996, pp. 516-523.					
JL	AR	Lim, S. et al., "Application of Alternating Phase-Shifting Masks to 200nm Contact Holes", SPIE Vol. 2884, July 1996, pp. 243-254					
EXAMINER <i>A. Zorascu</i>				DATE CONSIDERED <i>11/6/03</i>			
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant							